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Compositional stability of FePt nanoparticles on SiO$_2$/Si during annealing

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The loss of Fe due to oxidation or diffusion into the substrate can prevent the successful preparation of well-ordered, stoichiometric, FePt nanoparticles. In this work we report the composition changes during annealing observed for small (<10 nm) FePt nanoparticles on thermally grown SiO$_2$ layers on Si wafer substrates. Additionally, we describe the use of a controlled reducing gas mixture, Ar+H$_2$+H$_2$O, to reduce the loss of Fe. © 2006 American Institute of Physics.

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I. INTRODUCTION

FePt alloys consisting of the chemically ordered $L1_0$ phase are of interest for ultrahigh magnetic recording media applications due to the high magnetocrystalline anisotropy ($\sim$10$^7$–10$^8$ ergs/cm$^3$) of this tetragonal crystal structure. Typically, the synthesis of ordered $L1_0$ FePt nanoscale materials involves the preparation of A1 (fcc) phase FePt thin film or nanoparticle samples, and subsequent annealing to allow the fcc to $L1_0$ phase transformation. During this process, control of the chemical stoichiometry should be maintained because of the strong dependence of the chemical order and uniaxial magnetic anisotropy on stoichiometry.$^{1,4}$ However, few reports have been published on the compositional stability during annealing of FePt nanoscale samples. Thomson et al. reported the formation of Fe silicides due to the high-temperature annealing for FePt thin films on a Si substrate, which caused a substantial drop in magnetization.$^5$ While thermally grown SiO$_2$ layers are commonly used with Si wafer substrates to prevent silicide formation, quantitative reports on the effectiveness of the SiO$_2$ layer to maintain sample stoichiometry are absent.

In this paper we report the compositional stability of FePt nanoparticles on SiO$_2$/Si substrates during annealing in a reducing gas, consider possible mechanisms of Fe loss, and describe a controlled reducing gas annealing that improves compositional stability. Analytical transmission electron microscopy (TEM) was used to quantify the compositions of FePt nanoparticles prepared on thin (31 nm) SiO$_2$ layers. A loss of Fe during annealing at 750 °C in 97% Ar+3% H$_2$ was observed. The diffusion of Fe into the SiO$_2$ layer and chemical reaction of Fe with the SiO$_2$/Si substrate were considered to be likely mechanisms for the Fe loss. The diffusion of Fe across the thermally grown SiO$_2$ layer was observed for a relatively thick (8 nm) FePt deposit on a thin SiO$_2$ layer. Annealing with a controlled reducing gas mixture of Ar+H$_2$+H$_2$O was explored to reduce the loss of Fe during annealing. In the presence of the uncontrolled trace levels of water vapor expected during annealing, a high H$_2$ partial pressure can favor the formation of iron silicide, while a low H$_2$ partial pressure may allow the formation of iron oxide. Based on simple thermodynamic considerations, a ratio of H$_2$ partial pressure to that of H$_2$O between 1.0 and 2.4 should be maintained for maximum stability of FePt in the presence of SiO$_2$. FePt nanoparticles on thin SiO$_2$ (31 nm) have been so annealed and the stability of the stoichiometry confirmed by analytical TEM. We conclude that the loss of Fe into SiO$_2$/Si is a concern for the compositional stability of single layers of FePt nanoparticles during high-temperature annealing and that control of the annealing gas ambient can significantly improve compositional stability.

II. EXPERIMENT

The Fe$_{90}$Pt$_{50}$ deposits were prepared at room temperature by DC co-sputtering of Fe and Pt from elemental targets. The initial deposit was not a continuous film, rather a collection of nanoparticles and/or a discontinuous thin film. The base pressure of the sputtering system was in the 10$^{-8}$ Torr range prior to the introduction of the Ar sputtering gas at a pressure of 3 mTorr and a flow rate of 20 SCCM (standard cubic centimeter per minute). The amounts of FePt deposited corresponded to thicknesses of 0.25, 2, and 8 nm. The 0.25-nm- and 8-nm-thick films were deposited onto oxidized Si(100) wafers with an oxide thickness of 31 nm, while that for 2-nm-thick film was more than 100 nm. Film compositions were calibrated by Rutherford backscattering spectrometry (RBS). The uncertainties in elemental concentrations were ±0.5 at. % for both the Fe and Pt.
As is commonly done,\textsuperscript{6} FePt nanoparticle samples were annealed at atmospheric pressure with a reducing gas flow to prevent the film from oxidizing. In our experiments a reducing gas of 97% Ar+3% H\textsubscript{2} was used for annealing of 750 °C for 20 h. While some trace levels of water vapor are expected to be present, the H\textsubscript{2}O vapor pressure is not controlled and concentration in the gas flow is very low, and this procedure is referred to as an uncontrolled reducing gas annealing. For this annealing condition a loss of Fe can be observed for FePt nanoparticles, as described below.

Experiments using a more controlled reducing gas annealing condition were also performed. For these experiments, an intentionally higher and controlled H\textsubscript{2}O vapor pressure was used in conjunction with the 97% Ar+3% H\textsubscript{2} reducing gas to reduce the possible formation of silicides, as well as oxides, during high-temperature annealing.

A thermodynamic model of the chemical reactions of Fe, Si, H, and O is described below to illustrate the advantages of a controlled reducing gas annealing for FePt nanoparticle processing. This very simplified model assumes that the Pt does not participate, that the Fe present is available as elemental Fe, that the available bulk thermodynamic data are representative of thin films, and that mixtures (e.g., Si\textsubscript{x}Fe\textsubscript{1-x}O\textsubscript{y}) and other phases do not form. The reactions that are considered are the formation of an iron silicide with the reduction of SiO\textsubscript{2}, Eqs. (1) and (2), and the formation of iron oxide by reaction with water vapor, Eq. (3). Qualitatively, in a strongly reducing ambient, the reduction of SiO\textsubscript{2} makes Si available and promotes the formation of FeSi, while in a nonreducing ambient water vapor is able to oxidize Fe and form FeO.

\begin{equation}
\text{Fe} + \text{SiO}_2 + 2\text{H}_2 \leftrightarrow \text{FeSi} + 2\text{H}_2\text{O},
\end{equation}

\begin{equation}
\text{Fe} + 2\text{SiO}_2 + 4\text{H}_2 \leftrightarrow \text{FeSi}_2 + 4\text{H}_2\text{O},
\end{equation}

\begin{equation}
\text{Fe} + \text{H}_2\text{O} \leftrightarrow \text{FeO} + \text{H}_2.
\end{equation}

Quantitative thermodynamic calculations using the data from Ref. 7 suggest that a ratio of H\textsubscript{2} partial pressure to that of H\textsubscript{2}O between 1.0 and 2.4 should be maintained to prevent both silicide formation [reactions (1) and (2)] and oxide formation [reaction (3)]. Higher H\textsubscript{2} partial pressure favors the formation of iron silicide, while a lower H\textsubscript{2} partial pressure favors iron oxide formation. The possible reactions in our real FePt nanoparticle/substrate system are much more complex than allowed for by the simple model above. However, the ratio of H\textsubscript{2}/H\textsubscript{2}O calculated should represent a value appropriate for minimizing reactions between the nanoparticles and the substrate. For an annealing gas of Ar+3% H\textsubscript{2} gas at 1 atm, the desired range of H\textsubscript{2}O partial pressure conveniently corresponds to the saturated vapor pressure of H\textsubscript{2}O between 25 and 13 °C. Thus, a suitable H\textsubscript{2}/H\textsubscript{2}O partial pressure ratio is readily obtained by the use of a room-temperature water bubbler.

We have used both controlled and uncontrolled reducing gas annealing in our laboratory for a variety of investigations of FePt nanoparticles and report here on the characterization of five samples (identified as A, B, C, D, and E) by analytical TEM. The nominal FePt deposit thicknesses, SiO\textsubscript{2} membrane layer thicknesses, and annealing conditions for these samples are listed in Table I. The samples were analyzed using a Tecnai F30 TEM. Its energy dispersive x-ray (EDX) detector was used to determine the compositions of individual particles, and another detector, high-angle annular dark field (HAADF), was used for Z-contrast images.

\begin{table}[h]
\centering
\caption{Table I. FePt sample list, with as-deposited composition of Fe\textsubscript{50}Pt\textsubscript{50}.}
\begin{tabular}{|c|c|c|c|c|}
\hline
Nominal FePt thickness (nm) & SiO\textsubscript{2} thickness (nm) & Temperature (°C) & Time (h) & Gas \\
\hline
Sample A & 4 & 31 & N/A & N/A & N/A \\
Sample B & 0.25 & 31 & 750 & 20 & Ar/H\textsubscript{2} \\
Sample C & 0.25 & 31 & 750 & 20 & Ar/H\textsubscript{2}/H\textsubscript{2}O \\
Sample D & 8 & 31 & 750 & 20 & Ar/H\textsubscript{2} \\
Sample E & 2 & >100 & 750 & 20 & Ar/H\textsubscript{2} \\
\hline
\end{tabular}
\end{table}

\begin{figure}[h]
\centering
\includegraphics[width=0.8\textwidth]{fig1.png}
\caption{FIG. 1. TEM image and EDX spectrum of sample A. (a) HAADF image indicating region sampled and (b) EDX spectrum.}
\end{figure}

\begin{figure}[h]
\centering
\includegraphics[width=0.8\textwidth]{fig2.png}
\caption{FIG. 2. TEM image and EDX spectrum of indicated individual FePt nanoparticle for sample B.}
\end{figure}

III. RESULTS AND DISCUSSION

Figure 1 shows the HAADF image and EDX spectrum of the as-deposited 4-nm-thick Fe\textsubscript{50}Pt\textsubscript{50} thin film (sample A). The integrated intensities of Fe \textit{K}α and Pt \textit{L}α peaks were used to determine the \textit{K} factor of these two elements according to Cliff-Lorimer equation,\textsuperscript{8} which gives a value of...
ordered, stoichiometric, FePt nanoparticles. In this work we report the composition changes observed for small (<10 nm) FePt nanoparticles on thermally grown SiO2 layers on Si wafer substrates. For nanoparticles prepared on thin (31 nm) SiO2 layers, a loss of Fe during annealing at 750 °C in Ar+3% H2 was observed by analytical transmission electron microscopy (TEM). Probable factors contributing to this composition change were carefully examined. It was found that diffusions and chemical reactions of Fe and Si/SiO2 substrates may be responsible for this change. A similar loss for nanoparticles on thicker (>100 nm) SiO2 was not detected by EDX, but should not be presumed negligible. The diffusion of Fe across SiO2 was confirmed for a relatively thick (8 nm) FePt deposit on the thinner SiO2 by the observation of iron-rich precipitates within the Si wafer.

Wet annealing was explored to prevent the loss of Fe during annealing. Based on thermodynamic considerations, a ratio of H2 partial pressure to that of H2O between 1.0 and 2.4 should be maintained. FePt nanoparticles on thin SiO2 (31 nm) have been so annealed and an improved stability of the stoichiometry was confirmed by analytical TEM. We conclude that the loss of Fe into SiO2/Si is a concern for the compositional stability of single layers of FePt nanoparticles during high-temperature annealing and that control of the annealing gas ambient may improve compositional stability.

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